

## CLAIMS

What is claimed is:

1 1. A surface metrology device, comprising:

2 a metrology unit receiving information from a measurement region of a surface; and

3 a first imaging camera with a first field-of-view containing the measurement region.

1 2 A semiconductor processing device, comprising:

2 a wafer process station; and

3 a metrology station apart from but coupled to the process station wherein the  
4 metrology station comprises an ultraviolet light source illuminating a measurement region of a  
5 surface. 200 - 400 nm

1 3. A semiconductor processing device, comprising:

2 a wafer process station; and

3 a metrology station apart from but coupled to the process station wherein the  
4 metrology station comprises an ultraviolet light source illuminating a measurement region of a  
5 surface and at least one spectrograph optically coupled to the measurement region of the  
6 surface.

1 4. A semiconductor processing device, comprising:

2 a wafer process station; and





